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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Mark Leonard O'Neill, et al.	
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U.S. PATENT DOCUMENTS

EXAM- INER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPRO- PRIATE
Tam	6 1 4 7 0 0 9	11/14/00	Grill, et al	438	780	6/29/98
	6 1 5 9 8 7 1	12/12/00	Loboda, et al	438	786	5/29/98
	6 0 7 7 5 7 4	6/20/00	Tatsuya Usami	427	579	8/18/97
	6 0 5 4 3 7 9	4/25/00	Yau, et al	438	623	2/11/98
	5 9 8 9 9 9 8	11/23/99	Sugahara, et al	438	623	8/28/97
	6 0 7 2 2 2 7	6/6/00	Yau, et al	257	642	7/13/98
	5 8 7 2 0 6 5	2/16/99	V. Sivaramakrishnan	438	784	4/2/97
	5 8 2 7 7 8 5	10/27/98	Bhan, et al	438	784	10/24/96
	5 7 0 3 4 0 4	12/30/97	M. Matsuura	257	758	12/24/96
	5 7 0 0 7 3 6	12/23/97	M. Muroyama	438	622	12/11/95
	5 5 7 1 5 7 6	11/5/96	Qian, et al	427	574	2/10/95
	5 6 6 1 0 9 3	8/26/97	Ravi, et al	438	763	9/12/96
Tam	5 8 0 0 8 7 7	9/1/98	Maeda, et al	427	535	8/9/96

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
					YES NO
Tam	9 9 4 1 4 2 3	8/19/99	WO	C23C	X
	8 1 5 0 0 3 6	6/2/98	JP	H01L	21/31 6 X
	9 6 3 2 1 4 9	12/3/96	JP	H01L	21/31 4 X
	9 9 1 1 1 7 1	4/23/99	JP	H01L	21/316 X
Tam	9 9 1 1 1 7 1	4/23/99	JP	H01L	21/316 X

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Tam	"Recent Progress In PECVD Low-k Dielectrics for Advanced Metallization Schemes", Lee, et al. (no data available)
	"Addressing The Challenges..", micromagazine.com MICRO February 2001.
	Japanese Journal of Applied Physics, Vol. 38 (1999) PP. 2368-2372.
	Japanese Journal of Applied Physics, Vol. 37 (6369-6373. (1998)
	Electrochemical Soc. Proceedings Vol. 98-3. PP 163-168. (1998)
	Japanese Journal of Applied Physics Vol. 38 (1999) PP. 4520-4526.
	IEEE Intl. Conference Conduction and Breakdown... June 1998, Vasteras, Sweden
	Japanese Journal of Applied Physics Vol. 37 (1998) PP 4904-4909.
	Journal of Applied Physics Vol. 87, No. 8, 15 April 2000.
	Thin Solid Films 337 (1999) PP. 67-70.
	Mat. Res. Soc. Symposium Proc. Vol. 606, PP 57-62. (no data available)
	"PE-CVD of Fluorocarbon/SiO...", Plasmas and Polymers, Vol. 4, No. 1, 1999
Tam	"Low Dielectric Constant CF/SiOF...", Yun, et al, Thin Solid Films 341 (1999) PP 109-111.

EXAMINER	DATE CONSIDERED 12/10/02
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EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.